## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

pplication of:

GERALD DEBOY et al.

Serial No.: 10/633,044

Filed: August 1, 2003

Title: "Power Factor correction Circuit§ WITH HIGH-VOLTAGE SEMICONDUCTOR§

COMPONENT"

Group Art Unit:

2815

Examiner:

Wilson, Allan R.

Attorney Docket No.: 068758.0134

CERTIFICATE OF MAILING VIA EXPRESS MAIL 37 C.F.R. §1.10

PURSUANT TO 37 CFR 1.10, I HEREBY CERTIFY THAT I HAVE KNOWLEDGE AND A REASONABLE BASIS FOR BELIEF THAT THIS CORRESPONDENCE IS BEING DEPOSITED WITH THE UNITED STATES POSTAL SERVICE AS EXPRESS MAIL POST OFFICE TO ADDRESSEE ON THE DATE INDICATED BELOW, AND IS ADDRESSED

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## INFORMATION DISCLOSURE STATEMENT

Sir:

Applicants respectfully request, pursuant to 37 C.F.R. §§1.56, 1.97 and 1.98, that the art listed on the attached PTO-1449 forms be considered and cited in the examination of the aboveidentified divisional patent application.

In accordance with 37 C.F.R. §1.98(d)(1), copies of the one hundred thirty seven (137) cited art references on the attached eight (8) pages of Form PTO-1449 are not attached hereto, as each of these one hundred thirty seven (137) references was previously submitted by the Applicant, in the parent patent application U.S.S.N. 09/786,022, filed April 22, 1999, which has now been allowed and is hereby properly identified according to 37 C.F.R. §198(d)(1).

**PATENT** 

Furthermore, pursuant to 37 C.F.R. §§1.97(g) and (h), Applicants do not represent

that a search has been made and do not admit that these references are, or are considered to be,

material to the patentability of the present divisional application.

As this Information Disclosure Statement is being submitted before the mailing of

the first office action on the merits, Applicants believe that no fee is due. However, should the

Commissioner deem that a fee is due, Applicants respectfully request that the Commissioner accept

this as a Petition Therefor, and authorize the Commissioner to charge any fees due to Baker Botts

By:

L.L.P. Deposit Account No. 02-0383, Order No. 068758.0134.

Respectfully submitted,

BAKER BOTTS L.L.P. (023640)

Date: November 4, 2003

Andreas H. Grübert

(Limited recognition 37 C.F.R. §10.9)

One Shell Plaza

910 Louisiana Street

Houston, Texas 77002-4995

Telephone:

713.229.1964

Facsimile:

713.229.7764

AGENT FOR APPLICANTS

Sheet \_\_1\_ of \_8 Application Number Docket Nurrber (Optional) Form PTO-1449 INFORMATION DISCLOSURE CITATION 068758.0102 09/786,022 IN AN APPLICATION (Use several sheets if necessary) Applicant Deboy et al. Filing Date 04/22/99 Group Art Unit: **U.S. PATENT DOCUMENTS** CLASS SUB-FILING DATE IF DATE NAME DOCUMENT **EXAMINER** INITIAL NUMBER **CLASS** APPROPRIATE 3,171,068 02/23/65 Denkewalter et al. 317 234 10/19/60 07/12/73 3,925,803 12/09/75 Kobayashi 357 22 357 50 10/31/74 3,961,356 06/01/76 Okuhura et al. 52 11/01/74 4,003,072 01/11/77 Matsushita et al. 357 Jambotkar 29 571 12/13/76 4,055,884 11/01/77 02/07/78 357 23 04/22/77 4,072,975 Ishtiani 07/18/78 Tihanyi 357 23 03/09/77 4,101,922 03/20/79 Jambotkar 357 23 08/08/77 4,145,700 05/03/79 03/16/82 Nishizawa et al. 357 43 4,320,410 23 04/14/80 4,345,265 08/17/82 Blanchard 357 4,366,495 12/28/82 Goodman et al 357 23 08/06/79 357 23 02/09/81 4,376,286 03/08/83 Lidow et al. Translation SUB-COUNTRY **CLASS** DOCUMENT DATE **CLASS** NUMBER NO YES HOIL 29/06 EP 0 053 854 B1 16.06.82 **EPO** HOIL 29/78 GB 2 089 118 A 16.02.82 UK X HOIL 29/78 EP 0 069 429 A2 12.01.83 **EPO** HOIL 29/784 EP 0 447 873 A2 01.04.92 **EPO** 29/784 DE 43 09 764 A1 25.03.93 Germany HOIL х HOIL 29/78 DE 43 09 764 C2 29.9.94 Germany (Including Author, Title, Date, Pertinent Pages, Etc.) OTHER DOCUMENTS 1967 A.S. Grove: "Physics and Technology of Semiconductor Devices" p 78-83 B. Jayant Baliga, Sorab K. Ghandi: "Analytical Solutions for the Breakdown Voltage of 1976 Abrupt Cylindrical and Spherical Junctions" (p 739-744) 1977 Richard F. David: "Computerized Thermal Analysis of Hybrid Circuits" 27th Electronics Components Conference, May 16-18 1977 (p 324-332)

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP §609: Draw line through citation if not in conformance and not considered. Include copy of this form with next

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## INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(Use several sheets if necessary)

Application Number Docket Number (Optional) 068758.0102

09/786,022

Applicant Deboy et al.

Filing Date 04/22/99 Group Art Unit:

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# INFORMATION DISCLOSURE CITATION IN AN APPLICATION

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 Docket Number (Optional)
 Application Number

 068758.0102
 09/786,022

Applicant Deboy et al.

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Applicant Deboy et al.

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437	31	08/07/92				
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Docket Number (Optional) Application Number Form PTO-1449 INFORMATION DISCLOSURE CITATION 068758.0102 09/786,022 IN AN APPLICATION (Use several sheets if necessary) Applicant Deboy et al. Filing Date 04/22/99 Group Art Unit: U.S. PATENT DOCUMENTS CLASS SUB-FILING DATE IF DOCUMENT DATE NAME **EXAMINER** APPROPRIATE CLASS NUMBER INITIAL Translation SUB-**CLASS** DOCUMENT DATE COUNTRY **CLASS** NUMBER NO YES (Including Author, Title, Date, Pertinent Pages, Etc.) **OTHER DOCUMENTS** Zahir Parpia, C. Andre T. Salama, Robert A. Hadaway, "A CMOS-Compatible High-Oct. 1988 TEEE Voltage IC Process" (p 1687-1694) Chen Xingbi, Li Zhaoji, Li Zhongmin: "Breakdown Voltage of Cylindrical Boundary Chinese 1989 Abrupt Junctions" (p 463-465) Journal of H.R. Chang, F.W. Holroyd: "High Voltage Power MOSFET's with a Trench-Gate Solid State 1990 Structure" (p 381-387) Electronics Li Zhoaji, Yu Hongquan, Chen Xingbi: "Temperature Distribution of Full Thermal Path of Chinese 1990 Journal of VDMOS" (p 435-440) Article by Xing-Bi Chen presented at 2<sup>nd</sup> German-Chinese Electronics Week Congress, 1991 Shanghai, China. 1992 Zhang Bo, Chen Xingbi, Li Zhaoji: "Two Dimensional Electric Field Analysis of JTE Chinese Journal of Junctions" (p. 626-632) X.B. Chen et al., "Theory of a novel voltage-sustaining layer for power devices" (from 1998 Microelectronics Journal) Deboy et al. article, "A New Generation of High Voltage MOSFETs breaks the Limit Line of Silicon" published by IEEE (2nd, color copy added, 2nd set of Bates ranges correspond) Lorenz et al. article, "Drastic Reduction of On-Resistance with CoolMOS" in PCIM Europe 1998 Claus Geisler, "Birth of the Cool in MOS" May 1998 X.B. Chen, P.A Mawby, K. Board et. al, "Theory of a Novel Voltage-Sustaining Layer for 1998 Power Devices" (from Microelectronics Journal) Article, "Siemens Introduces new Generation of High-Voltage MOSFET Technology" May 1998 Article, "Siemens' new MOSFET design drastically cuts on-state resistance" May 1998 Chen article, "Theory of a Novel Voltage Sustaining (CB) Layer for Power Devices" (from July 1998 Chinese Chinese Journal of Electronics) Journal of Steve Bush, "Five-fold resistance cut for high-voltage FETs" July 1998 DATE CONSIDERED EXAMINER EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP §609: Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant

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